

ABSTRACT

Provided is a method for producing a polishing slurry, polishing abrasive particles, and a polishing slurry, according to which a polishing rate is improved, and the formation of marks on a glass substrate can be suppressed. Also provided is a method for manufacturing a glass substrate using such a polishing slurry and polishing abrasive particles. The method for producing the polishing slurry of the present invention is a method for producing a polishing slurry including polishing abrasive particles for use in processing for polishing a glass substrate, including: adding processing in which binders are added to a raw-material slurry including raw-material abrasive particles serving as a raw material for the polishing abrasive particles; drying processing in which the raw-material slurry including the binders is dried to produce a mass of the raw-material abrasive particles including the binders; and firing processing in which the mass of the raw-material abrasive particles is fired to produce a cluster of the raw-material abrasive particles including the binders. [Fig. 1]